

What is claimed is:

1. An exposure apparatus comprising:

an exposure region for irradiating exposure light to a substrate via an optical system and a liquid, and

5 a measurement region for obtaining information relating to the position of the substrate in advance of exposure, wherein

the exposure apparatus moves the substrate between the exposure region and the measurement region to perform exposure of the substrate, wherein

the exposure apparatus further comprising:

10 a penetration shielding mechanism that prevents the penetration of the gas in the vicinity of the exposure region to the measurement region.

2. An exposure apparatus according to Claim 1, wherein

the penetration shielding mechanism is an air conditioning system provided on

15 the exposure apparatus.

3. An exposure apparatus according to Claim 2, wherein the air conditioning system further comprises:

a chamber, which includes the exposure region and the measurement region, and

20 a blower part that makes gas within the chamber flow from the measurement region toward the exposure region.

4. An exposure apparatus according to Claim 3, wherein

the blower part further comprising:

25 an intake port formed on the measurement region side, and

an exhaust port formed on the exposure region side.

5. An exposure apparatus according to any one of Claims 2 to 4, wherein
the air conditioning system comprises a shielding part that prevents the passage
5 of gas between the exposure region and the measurement region.

6. An exposure apparatus according to Claim 5, wherein
the shielding part is an air curtain.

10 7. An exposure apparatus according to any one of Claims 2 to 6, wherein
an intake port and an exhaust port are respectively formed in the exposure
region and the measurement region.

8. An exposure apparatus according to Claim 1, wherein
15 the penetration shielding mechanism further comprising:
a suction mechanism that sucks the gas of the exposure region.

9. An exposure apparatus comprising:
an exposure region for irradiating exposure light to a substrate via an optical
20 system and a liquid, and
a measurement region for obtaining information relating to the position of the
substrate in advance of exposure, wherein
the exposure apparatus moves the substrate between the exposure region and the
measurement region to perform exposure of the substrate, wherein
25 the exposure apparatus further comprising

an intake part that individually supplies a gas to the exposure region and the measurement region respectively.

10. An exposure apparatus according to Claim 9, wherein

5 the properties of the gas supplied to the exposure region and the gas supplied to the measurement region are mutually different.

11. An exposure apparatus comprising:

an exposure region for irradiating exposure light to a substrate via an optical
10 system and a liquid, and

a measurement region for obtaining information relating to the position of the substrate in advance of exposure, wherein

the exposure apparatus moves the substrate between the exposure region and the measurement region to perform exposure of the substrate, wherein

15 the exposure apparatus further comprising

an intake part, which supplies a gas to at least one of the exposure region and the measurement region, and

an exhaust part, which respectively independently exhausts the gas in the vicinity of the exposure region and the gas in the vicinity of the measurement region.

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12. An exposure apparatus according to any one of Claims 9 to 11, wherein

the exposure apparatus further comprising

a penetration shielding mechanism between the exposure region and the measurement region which prevents the gas in the vicinity of the exposure region from

25 penetrating to the measurement region.

13. A device manufacturing method that includes a lithography process, wherein an exposure apparatus of any one of Claims 1 to 12 is used in the lithography process.

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